

FIG. I

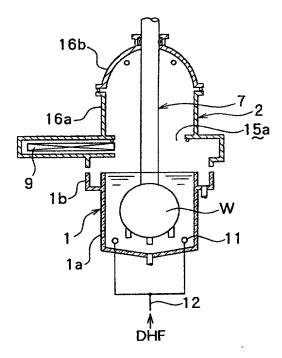


FIG. 2

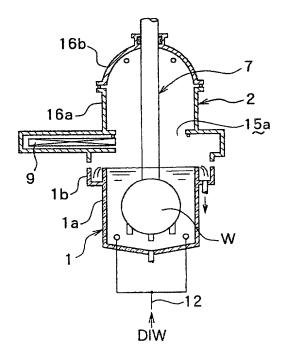
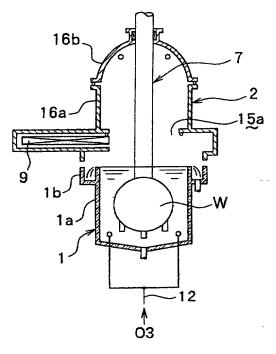


FIG. 3

3/13



F I G. 4

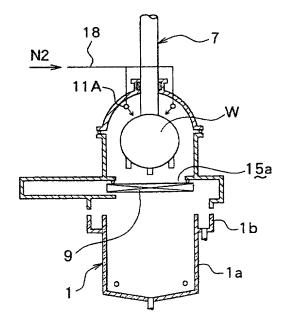


FIG. 5

Title: Method and Apparatus of Processing Surface of Substrate Inventor(s): TOSHIMA

Inventor(s): TOSHIMA Application No.: 10/036,787 Docket No.: 199372003600

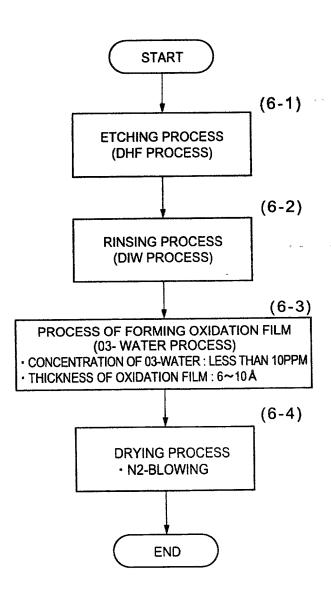
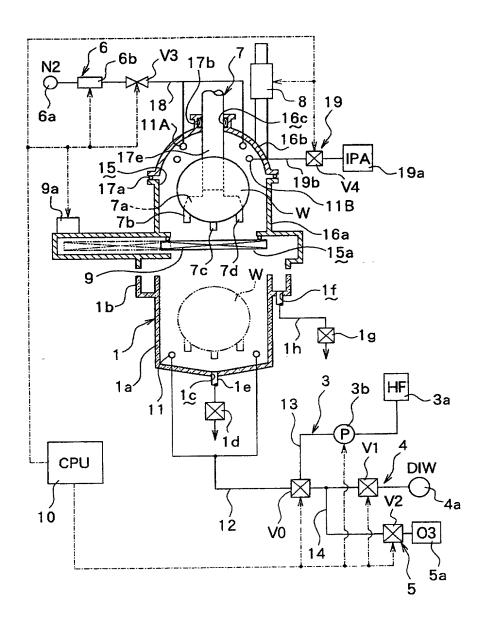
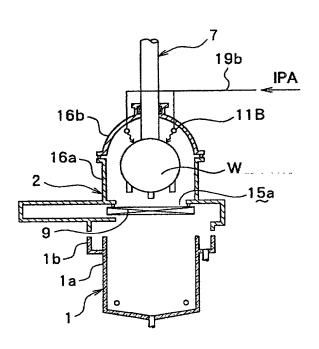


FIG.6

Docket No.: 199372003600



F1G.7



F1G. 8

Title: Method and Apparatus of Processing Surface of Substrate

Inventor(s): TOSHIMA Application No.: 10/036,787 Docket No.: 199372003600

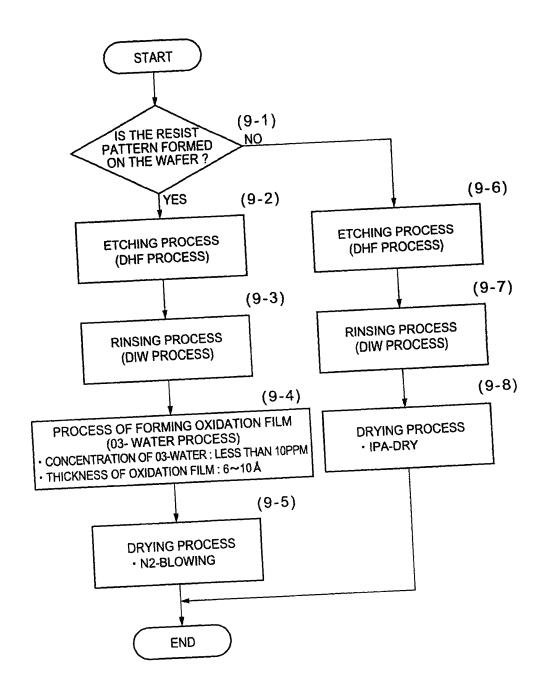
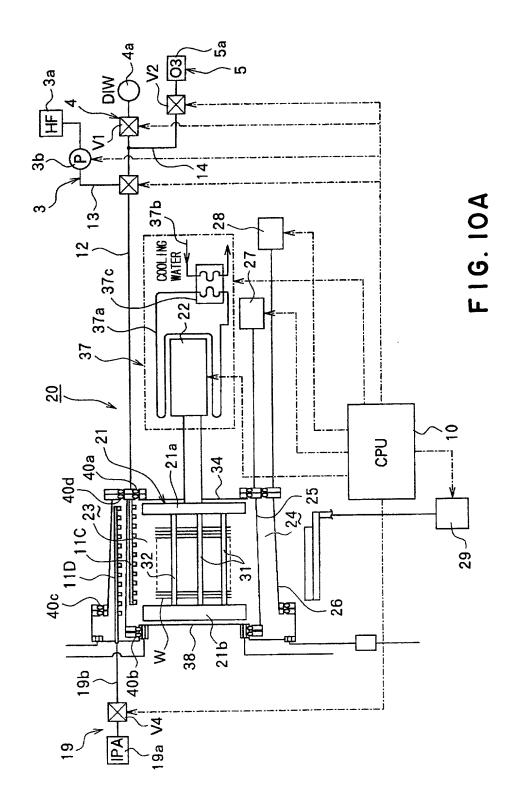
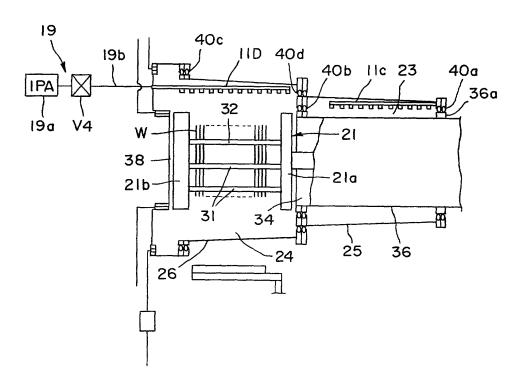


FIG.9



Title: Method and Apparatus of Processing Surface of Substrate

Inventor(s): TOSHIMA Application No.: 10/036,787 Docket No.: 199372003600



F I G. 10 B

Title: Method and Apparatus of Processing Surface of Substrate

Inventor(s): TOSHIMA Application No.: 10/036,787 Docket No.: 199372003600

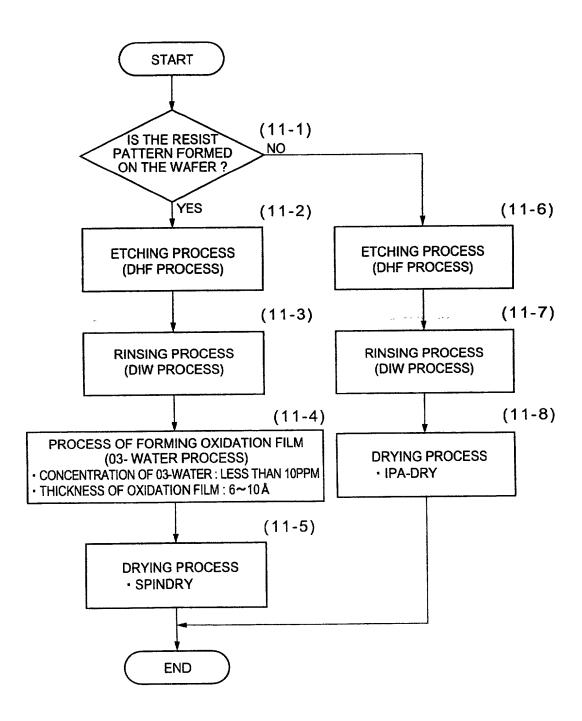
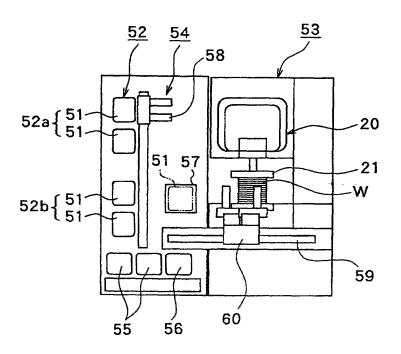
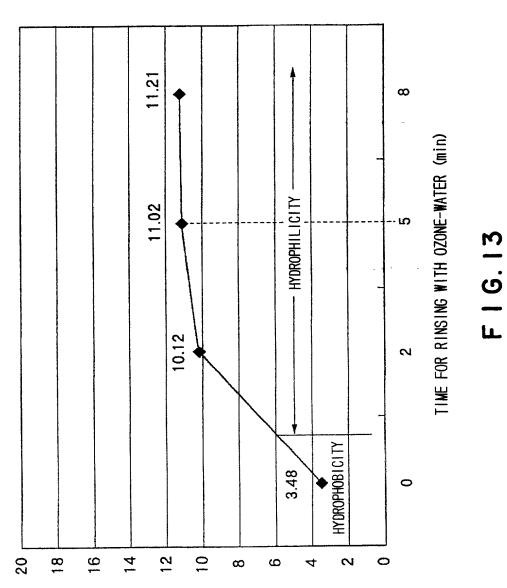


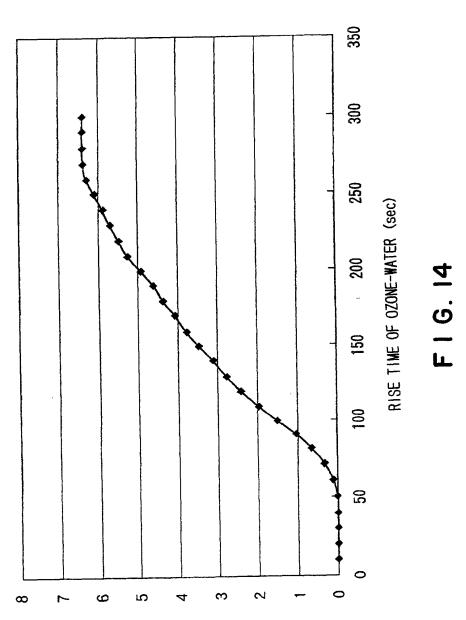
FIG.11



F1G. 12



THICKNESS OF OXIDATION FILM (Å)



CONCENTRATION OF OZONE-WATER (ppm)